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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Xu, Frank Y., et al.
Appl. No.: 10/789,319 GPAU.: 1712
Filed: 02/27/2004 Examiner: Marc S. Zimmer
Docket No.: P121-63-03 Conf. No.: 9202
For: Composition for an Etching Mask Comprising a Silicon-Containing Material

AMENDMENT

MAIL STOP AMENDMENT
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Office action mailed June 14, 2005,
Applicants respectfully request that the application be
amended as follows:

Amendments to the Specification begin on page 2 of this
paper.

Amendments to the Claims begin on page 6 of this paper

Remarks/Arguments begin on page 12 of this paper.

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